Biometric Quality Workshop

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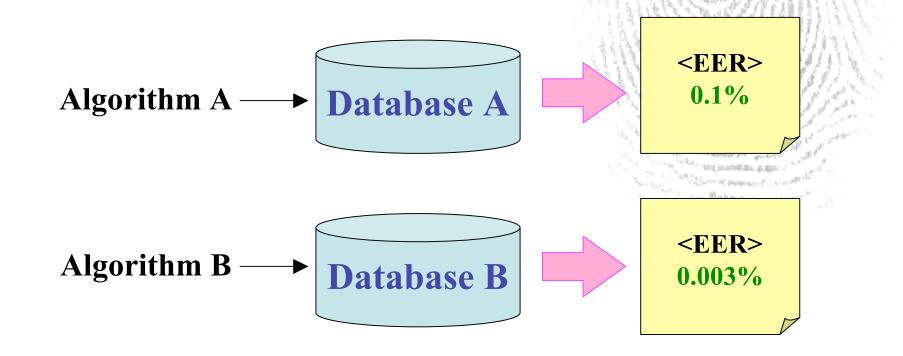
Inha University

&

Biometrics Engineering Research Center Korea

Introduction

Motivation 1

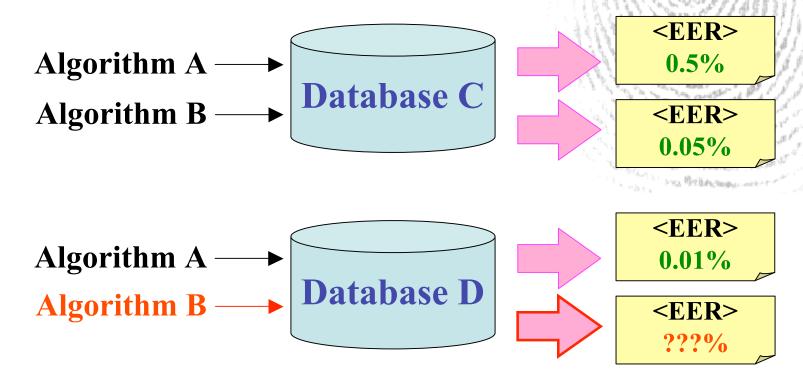


✓ Is Algorithm B better than Algorithm A?



Introduction

❖ Motivation 2



✓ Can I predict the performance of Algorithm B without actual testing over Database D?

Introduction

Purpose

To develop testing and evaluation methodologies for quantifying and comparing "Level of Difficulty (LoD)" of biometric databases t hat are collected for performance evaluation of biometric recognit ion algorithms

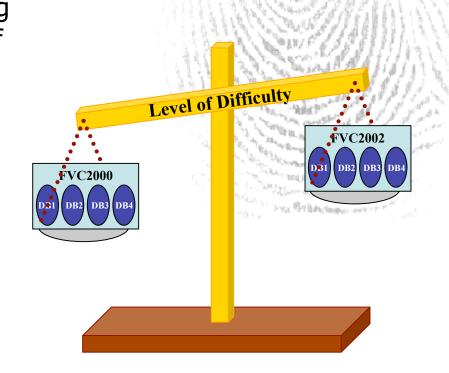
Scope

- Developing measures for evaluating LoD
 - Defining objective measures representing LoD
 - Quantifying the measures
- Developing methods for testing and evaluating LoD
 - Defining procedures for testing and reporting
 - Predicting the performance of recognition algorithms on differ ent databases



Definitions

- Level of Difficulty for biometric databases
 - Grades or scores quantifying the overall characteristics of biometric databases that influence the performance of biometric recognition algorithms
 - Integration of measures of various influencing factors which degrade the performance of genuine matching



- ✓ How to objectively measure the similarity of impostor pairs?
- ✓ Uniqueness is one of underlying hypothesis for biometrics.

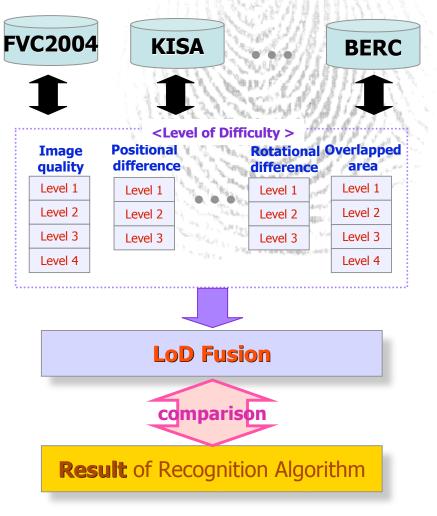
Definitions

Components of LoD

Attributes of a biometric datab ase that are to be measured in order to quantify its LoD

A subset of influencing factors to the performance of a recogn ition algorithm, which represen t differences between a pair of genuine biometric samples

LoD can be obtained by combining the measures of the attributes



Process of measuring and evaluating LoD

Sample Quality vs. DB Quality

Sample Quality	Database Quality (LoD)
Quality of a single image sample	 Aggregation of various differences between genuine pairs
Directly affects the performance of fea ture extractors, and indirectly affects t he matching performance	Directly affects the matching performance with no influence to feature extractor
	Quality of genuine sample pairs is a n important aspect of DB quality
Excellent Good Poor	Overlap=15.5% Score=2.5% Excellent Excellent

Definitions

- Examples for Component of LoD
 - Fingerprint Database
 - Distribution of sample quality
 - Co-occurrence of sample quality
 - Ratio of overlapped area
 - Translational difference
 - Rotational difference
 - etc.

- Face Database
 - Pose
 - Illumination
 - Facial expression
 - etc.

- Iris Database
 - Occlusion
 - Illumination
 - Focusing
 - etc.



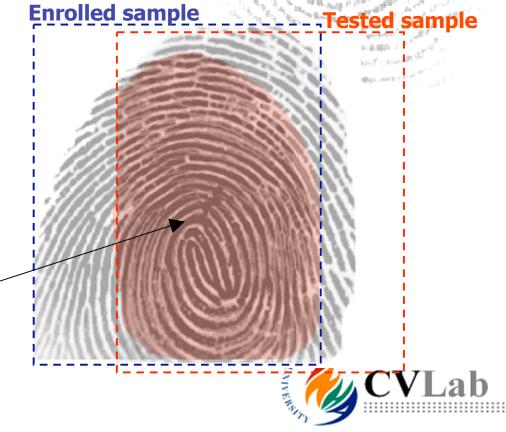
Components of LoD for Fingerprint

- \clubsuit Ratio of Overlapped area (R_o)
 - Step 1: Shift and rotate tested sample to find the same region of both enrolled sample and tested sample, which is overlapped are a
 - Step 2: Calculate the ratio of the overlapped area for target sam

 $R_o = \frac{P_{overlapped}}{P_{enrolled}} \times 100(\%)$

ple pair

Overlapped area



Components of LoD for Fingerprint

- Image quality of sample pairs
 - Ratio of Poor Pairing (RPP)

$$RPP = \frac{P_{Total} - P_{Good}}{P_{Total}} \times 100(\%)$$

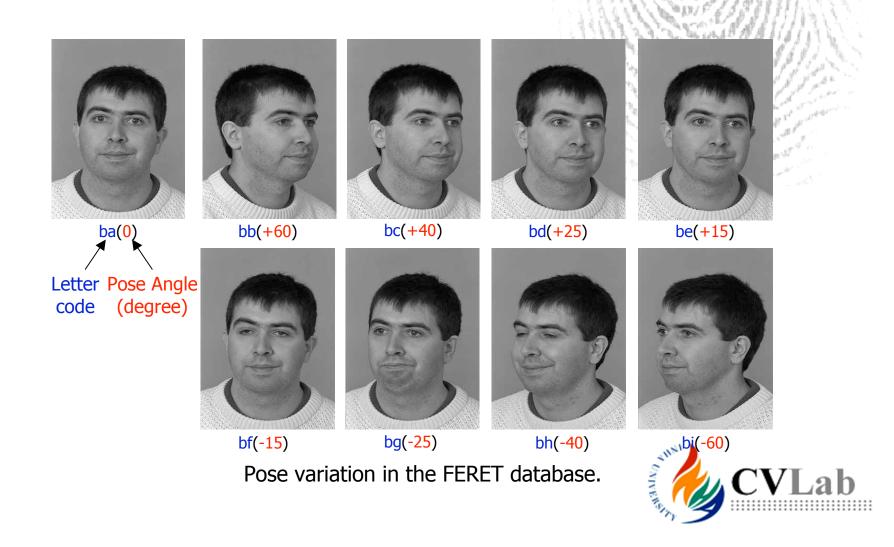
3 Levels of Poor Pairing

Quality co-occurrence matrix of genuine sample pairs

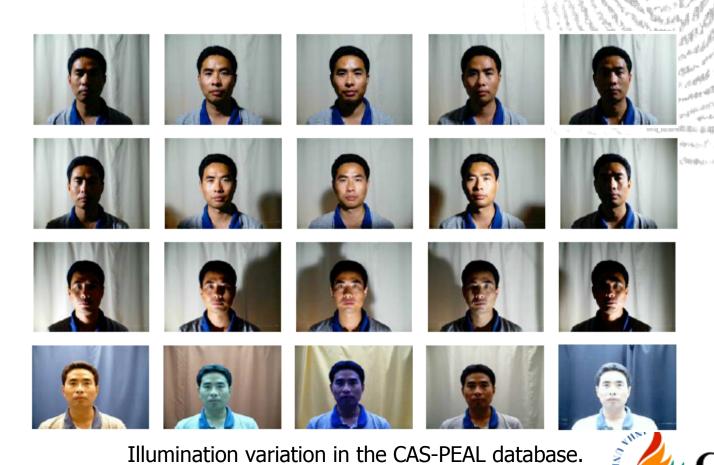
Enrolled Tes	Excellent	Very Good	Good	Fair	Poor	
Excellent	1171	331	134	16	7	
Very Good	472	305	120	8	1	Level 3
Good	123	47	48	6	6	
Fair	5	0	0	0	0	
Poor	0	0	0	0	0	



- \diamond Pose difference (P)
 - Feature information can be changed according to positions



- ❖ Illumination difference (I)
 - Change of feature information according to the brightness, color and loc ation of the light source.



- \Leftrightarrow Expression difference (E)
 - Change of feature information according to expression.





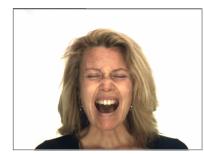




(b) Smile



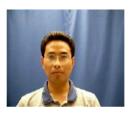
(c) Anger Expression variation in the AR database.

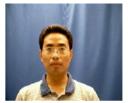


(d) Scream



- Other components
 - Accessory Variation













Accessory variation in the CAS-PEAL database.

Resolution



96 x 128



69 x 93



48 x 64



24 x 32

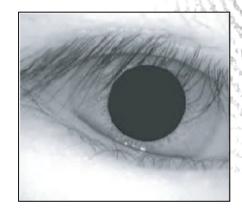
- Resolution variation image.
- Compression
- etc.



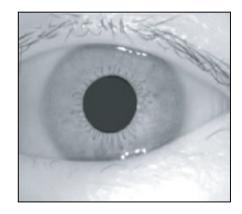
Components of LoD for Iris

- Occlusion
 - Pupil loss by eyelash interference
 - Blinking





❖ Non-uniform illumination

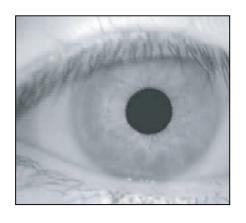


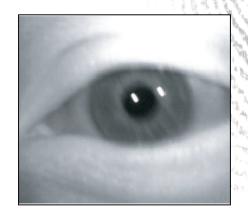




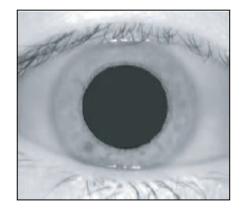
Components of LoD for Iris

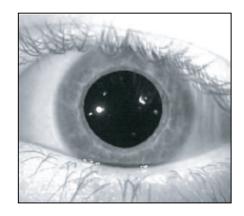
- Poor focusing
 - Eye motion and motion blur





Change in pupil area



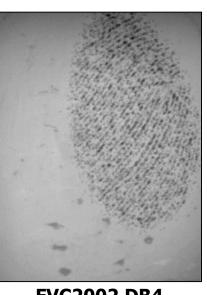




- Information of Experiments
 - Target databases
 - ◆ Three DB4s for FVC2000, 2002, 2004
 - Number of subjects
 - 100 per DB4
 - Number of impressions
 - 8 images per subject
 - Resolution
 - About 500 dpi



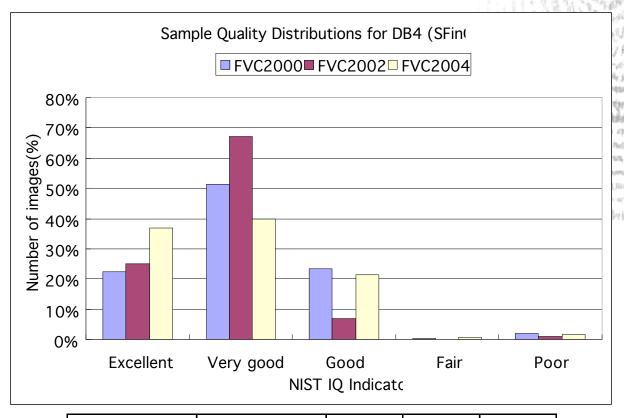
FVC2000 DB4



FVC2002 DB4

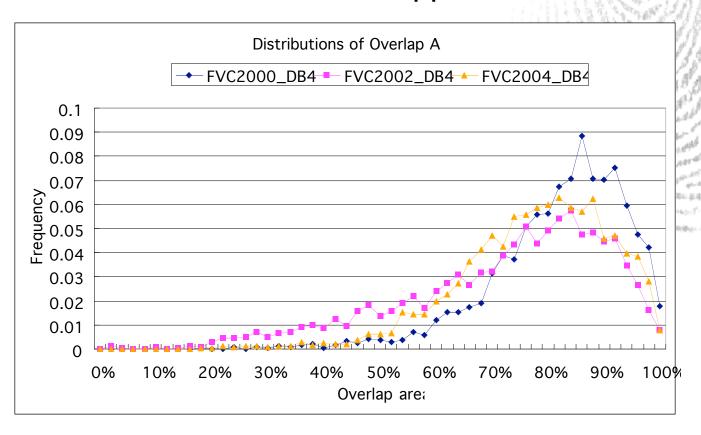


Distribution of Sample Quality



NIST IQ Indicator	NIST IO Level	FVC2000	FVC2002	FVC2004	ļ	
Excellent	1	180	200	294		
Verv good	2	412	537	320		
Good	3	188	55	170		
Fair	4	3		4	ZHZ)	
Poor	5	17	7	12	J. Charles	CVII ob
	Number of Images	800	800	800	E C	CYLAU
		2.59	% 1.0 °	% 2.0 9	10 or 1	

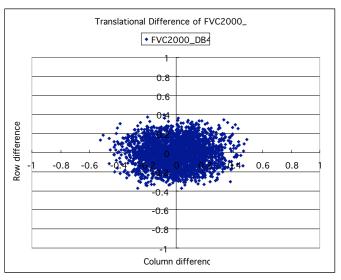
Distributions of Ratio of Overlapped Area

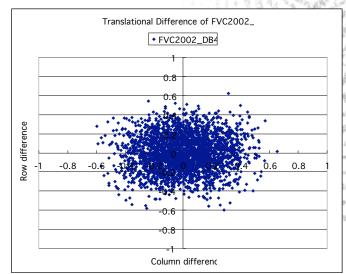


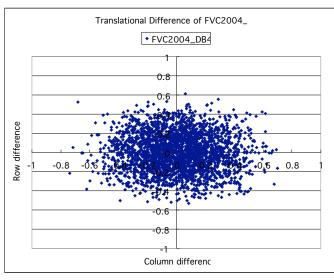
2002 > 2004 > 2000

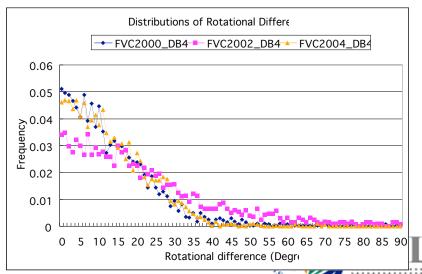


Distributions of Translational and Rotational Difference









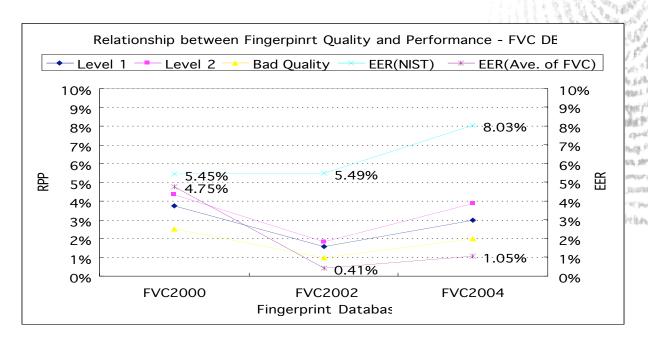
❖ Level-2 RPP

FVC2000 DB4	Poor	Fair	Good	Very Good	Excellent	Enrolled Tes
	6	0	61	215	322	Excellent
4.4%	3	0	250	947	266	Verv Good
Acres de la Constantina del Constantina de la Co	40	5	304	250	63	Good
	3	1	11	0	0	Fair
The second second second	14	0	28	6	5	Poor
FVC2002 DB4	Poor	Fair	Good	Very Good	Excellent	nrolled Tes
The second interest and the second in the se	8	0	12	275	380	Excellent
1.8%	5	0	98	1482	313	Verv Good
99.8 x	5	4	65	99	25	Good
	0	0	3	0	0	Fair
	5	0	9	5	7	Poor
FVC2004 DB4	Poor	Fair	Good	Very Good	Excellent	Enrolled Tes
	3	4	91	246	690	Excellent
>3.9%	13	7	228	605	216	Verv Good
	18	8	209	294	112	Good
	0	0	1	6	0	Fair
	1	2	20	20	6	Poor

2000 > 2004 > 2002



* Ratio of Poor Pairing vs. EER



DB4	Level 1	Level 2	EER	Ave. EER	Bad Ouality
FVC2000	3.75%	4.36%	5.45%	4.75%	2.50%
FVC2002	1.57%	1.82%	5.49%	0.41%	1.00%
FVC2004	2.96%	3.89%	8.03%	1.05%	2.00%



Intention

- To realize how much sample quality affects to the performance
- To find any other factors causing low genuine matching scores

Experiment

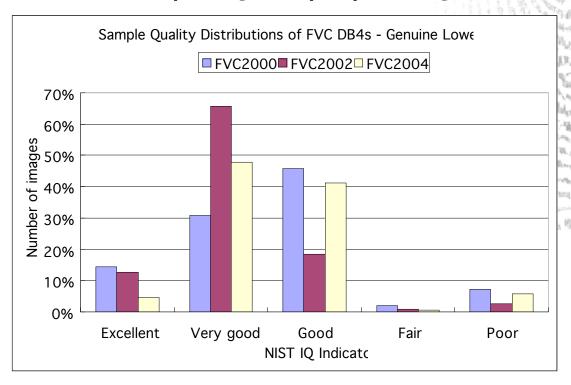
- Target DB: DB4(SFinGe) of FVC2000, 2002, 2004
- Sample Quality Measure: NFIQ
- Fingerprint Matcher: NIST's BOZORTH3

Analysis

- For the samples of bottom 5% scores in genuine matching, colle ct and analyze
 - Sample quality by NFIQ
 - Quality co-occurrence matrix of genuine pairs
 - Ratio of overlapped area of genuine pairs



Distribution of Sample Quality by NFIQ



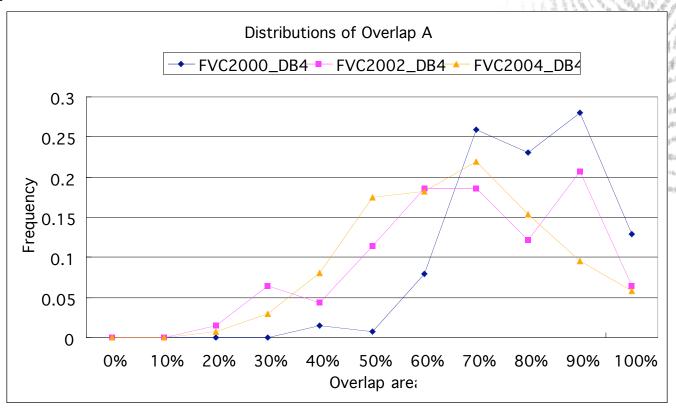
NIST IO Indicator	NIST IO Level	FVC2000	FVC2002	FVC2004	
Excellent	1	20	15	7	
Very good	2	43	78	73	
Good	3	64	22	63	
Fair	4	3	1	1	
Poor	5	10	3	9	21/21 A.
	Number of images			153	
		9.3	% 3.3 9	% 6.5	% ~ /// U V Lla
				7	89 _{77.} "

Quality Co-occurrence matrix of Genuine sample pairs

Enrolled Tes Excellent Very Good Good	t Excellent 5 2	Very Good 5 18	Good 4 18 45		Poor 2 0 13	FVC2000 DB4
<u>Fair</u>	0	0	4	0	2	
Poor	0	2	/	Ol	1	The second second
Enrolled Tes	t Excellent	Very Good	Good	Fair	Poor	FVC2002 DB4
Excellent	5	6	0	0		Fig. 5. Section of better the first section of the
Verv Good	4	66	13	91.4%	0	The second of th
Good	0	12	22	3	1	38.5 x
Fair	0	0	2	0	0	
Poor	2	1	2	0	0	
Enrolled Tes	t Excellent	Very Good	Good	Fair	Poor	FVC2004 DB4
Excellent	0	1	1	0	0	
Very Good	1	32	9	88.6%	1	
Good	5	28	47	1	7	
Fair	0	0	0	0	0	
Poor	0	3	3	O	0	

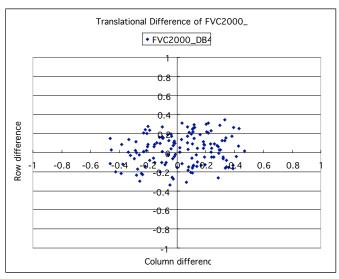
✓ In thses specific databases, there are a good portion of genuine pairs with "good quality pairing" but "low matching scores."

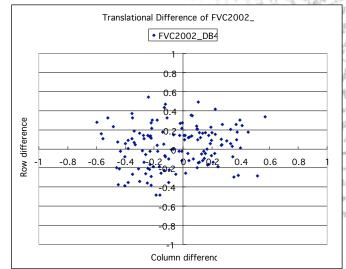
Distribution of Ratio of overlapped area between Genuin e pairs

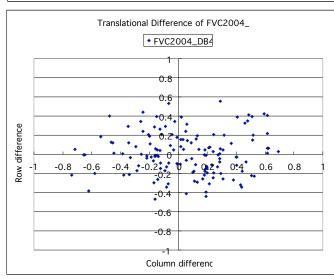


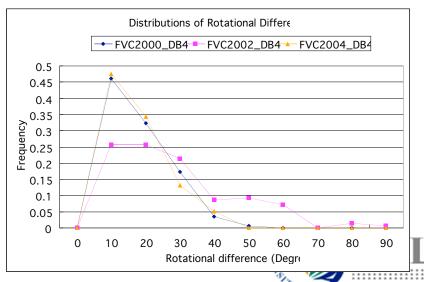


Distributions of Translational and Rotational Differences









- Quality-pairing of Low overlapped genuine pairs
 - For FVC2000 DB4

Overlap < 40%		2				
	Test Exce	llent V	ery Good	Good	Fair	Poor
Excellent		0	0	0	0	0
Very Good		0	0	1	0	0
Good		0	1	0	0	0
Fair		0	0	0	0	0
Poor		0	0	0	0	0

Overlap < 50%	3				
Enrolled Test	Excellent	Very Good	Good	Fair	Poor
Excellent	0	1	0	0	0
Very Good	0	0	1	0	0
Good	0	1	0	0	0
Fair	0	0	0	0	0
Poor	0	0	0	0	0





Quality-pairing of Low overlapped genuine pairs

For FVC2002 DB4

Overlap < 40%	17				
Enrolled Test	Excellent	Very Good	Good	Fair	Poor
Excellent	4	0	0	0	0
Very Good	2	9	0	0	0
Good	0	0	1	0	O
Fair	0	0	0	0	0
Poor	1	0	0	0	0

Overlap < 50%	33	r			
Enrolled Tes	t Excellent	Very Good	Good	Fair	Poor
Excellent	4	0	0	0	0
Very Good	2	22	1	0	0
Good	0	0	2	0	0
Fair	0	0	0	0	0
Poor	2	0	0	0	0



- Quality-pairing of Low overlapped genuine pairs
 - For FVC2004 DB4

Overlap < 40%	16)			K FORET
Enrolled Te	st Excellent	Very Good	Good	Fair	Poor
Excellent	0	1	0	0	O
Very Good	0	5	0	O	The contract of the contract o
Good	0	2	0	O	A Maria Maria
Fair	0	0	8	0	A The Manual Control
Poor	0	0	0	0	0

Overlap < 50%	40			***	**************************************
Enrolled Te	est Excellent	Very Good	Good	Fair	Poor
Excellent	0	1	1	0	0
Very Good	0	12	3	0	0
Good	1	6	14	0	1
Fair	0	0	0	0	0
Poor	0	1	0	0	0

√ Good Q-pair but low overlap → Low matching score



Observations

- Sample quality seems the most influencing factor to the perform ance with the underlying assumptions that enrolled samples are of good quality and have enough overlapped area with test sam ples.
- Nowever, the above assumptions do not hold in technology (off-line) evaluation where sample quality control is not in use.
- Even a genuine pair of excellent quality do not match.
- Ratio of overlapped area can be a factor to be considered for predicting the performance, especially in technology evaluation.



Conclusions

- Defines the quality of biometric databases, called Level of Difficulty.
- Proposes possible components of LoD for fingerprint.
- Demonstrates the automatic processes of measuring the components.
- How to combine the multiple components into a single L oD?
- How to predict the relative performance of a recognition algorithm based on LoD's?
- How to develop automatic processes of measuring LoD o f face and iris databases?



Thank you for attention!

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